

4A-PLASMA[®]

TECHNOLOGY & ENGINEERING

HiPIMS-PS

LEADING EDGE
TECHNOLOGY

Features:

HiPIMS-PS Uni-Polar / Bi-Polar

DC-PS (for magnetron sputtering, PECVD, Etch...)

DC-Pulsed-PS Uni-Polar / Bi-Polar (for magnetron sputtering, PECVD, Etch...)

HiPIMS-Bias / DC-Bias / DC - Pulsed- Bias (synchronization possible)

Single & Dual magnetron capability

NEW hiPlus⁺ - Technology Positive Voltage Reversal Option

with the PPP -Technology (Proportional Positive Pulse) and APP -Technology (Adjustable Positive Pulse) option.

Product Overview:

	hiP-V 6KW	hiP-V 10KW Opt.A	hiP-V 10KW Opt.B	hiP-V 20KW Opt.A	hiP-V 20KW Opt.B
Power	6KW	10KW	10KW	20KW	20KW
Peak Power	0,5MW	1,2MW	1,2MW	2,4MW	2,4MW
Voltage	1000V 1200V opt.	1000V 1200V opt.	1000V 1200V opt.	1000V 1200V opt.	1000V 1200V opt.
Current max. HiPIMS	500A	1000A	2000A	2000A	1000A
Current DC max.	18A	25A	25A	50A	50A
Frequency max.	2KHz	2KHz	1KHz	1KHz	2KHz
Time ON	5-1000µs	5-1000µs	5-1000µs	5-1000µs	5-1000µs
ARC Control	< 3µs	< 3µs	< 3µs	< 3µs	< 3µs
Cooling	Water	Water	Water	Water	Water

HiPIMS Power Packs up to 80KW & Customized Products Available

hiP-V Marketing & Sales c/o 4A-PLASMA; Aichtalstr. 66; D-71088 Holzgerlingen, Germany
Phone: +49-(0)7031-8175680; Fax: +49-(0)7031-8175681 email: info@4a-plasma.eu

www.4A-PLASMA.eu - info@4A-PLASMA.eu